



WEST Search History

DATE: Tuesday, June 25, 2002

L22 119 adj n	41 350 304 611 966	L24 L23 L22 L21
L23 120 or 121 or 12 2 L22 119 adj n	350 304 611	L23 L22
L22 119 adj n	304 611	L22
	611	
T 64		L21
L21 l18 adj n	966	
,		L20
L/19 al?sub.\$ 9	640	L19
£18 ga?sub.\$ 9	062	L18
L17 115 and 16	126	L17
L16 114 and 115	267	L16
L15 buffer 519	071	L15
L14 11 and 17	446	L14
L13 16 same 17	45	L13
L12 buffer near 17	7	L12
L11 11 and 16	31	L11
L10 L9	31	L10
L9 11 and 16	31	L9
L8 16 near 17	2	L8
L7 growth adj rate 200	018	L7
L6 13 or 14	056	L6
L5 13 and 14	6	L5
L4 a\$2sec	773	L4
L3 angstroms\$sec	289	L3
L2 angstom\$3 sec\$4	0	L2
L1 (gallium adj nitride) or gan	869	L1

END OF SEARCH HISTORY



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L28: Entry 55 of 256

File: USPT

Jun 6, 2000

DOCUMENT-IDENTIFIER: US 6072197 A

TITLE: Semiconductor light emitting device with an active layer

made of semiconductor having uniaxial anisotropy

Detailed Description Paragraph Right (37):

In this case, a growth <u>rate</u> of the n type A.sub.10.1 <u>Ga.sub.0.9 N</u> cladding layers 12, 16 is 0.6 to 5.5 .mu.m/hour, typically 2.6 .mu.m/hour; a growth <u>rate</u> of the GaN light guide layers 13, 15 is 0.5 to 5.2 .mu.m/hour, typically 2.4 .mu.m/hour; and a growth <u>rate</u> of the Ga.sub.0.9 In.sub.0.1 N active layer 14 is 0.1 to 1.5 .mu.m/hour, typically 0.6 .mu.m/hour.

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L28: Entry 196 of 256

File: USPT

Mar 11, 1986

DOCUMENT-IDENTIFIER: US 4575462 A

TITLE: Method of growing an alloy film by a layer-by-layer process on a substrate, and a method of making a semiconductor device

<u>Detailed Description Paragraph Right (4):</u>

The results shown in FIG. 2 give periods of oscillations during growth of the GaAs and (Ga,Al)As layers of 0.51 and 0.30 seconds respectively, and these periods correspond to growth rates of 1.99 .mu.m per hour of GaAs and of 3.40 .mu.m per hour of (Ga,Al)As (these growth rates have an accuracy of .+-.0.01 .mu.m/hour). Since the lattice constants of GaAs and AlAs are similar--they only vary by about 1%, the growth rate of (Ga,Al)As is the arithmetical sum of the growth rates of GaAs and AlAs. Subtracting the GaAs growth rate from the (Ga,Al)As growth rate gives an AlAs growth rate of 1.41 .mu.m/hour. Thus the composition of the (Ga,Al)As grown was calculated to be Ga.sub.0.585 Al.sub.0.415 As. The aluminium fraction of the film 29 was found to be 0.404 when measured by surface photovoltage, and an ion gauge flux monitor (not shown) used in the growth system gave an aluminium fraction of 0.405 (these aluminium fractions were accurate to .+-.0.01).

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L29: Entry 5 of 41

File: USPT

Nov 14, 2000

DOCUMENT-IDENTIFIER: US 6147363 A

TITLE: Nitride semiconductor light-emitting device and

manufacturing method of the same

<u>Detailed Description Paragraph Right (31):</u>

After completion of the light emitting layer 102, the substrate 100 was rapidly heated from 800 to 1100.degree. C. at a temperature increase rate of 100.degree. C./minute in an argon stream. The composition of the atmosphere of the MOCVD reaction system was changed to a mixture composed of argon and hydrogen during a waiting time of one minute at 1100.degree. C., and an aluminum gallium nitride mixed crystal layer (Al.sub.0.15 Ga.sub.0.85 N) layer 103 doped with magnesium (Mg) was deposited on the light emitting layer 102. The growth rate was set to about 3 nm/minute, which was 1.5 times faster than the growth rate of the light emitting layer 102. The growth was continued for 10 minutes to obtain a mixed layer of a thickness of about 30 nm. Bis-cyclopentadienylmagnesium (bis-(C.sub.5 H.sub.5).sub.2 Mg) was used as the doping source of magnesium. The supply amount of the magnesium doping source to the MOCVD reaction system was set to 8.times.10.sup.-6 mol/min. The concentration of magnesium atoms in the Mg doped aluminum gallium nitride layer 103 was determined as about 6.times.10.sup.19 atoms/cm.sup.3 by ordinary SIMS analysis.

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